Mid2 RC_part2

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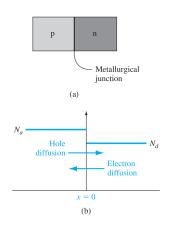
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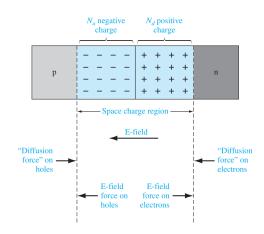
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Overview

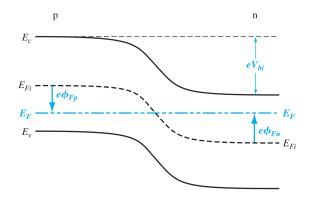
- Chapter 7
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Basic Structure





Zero Applied Bias



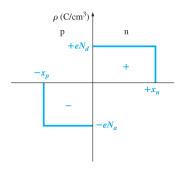
Built-in Potential Barrier

$$\begin{split} \phi_{Fn} &= -\frac{kT}{e} \ln(\frac{N_d}{n_i}) \\ \phi_{Fp} &= \frac{kT}{e} \ln(\frac{N_a}{n_i}) \\ V_{bi} &= |\phi_{Fn}| + |\phi_{Fp}| \\ &= \frac{kT}{e} \ln(\frac{N_a N_d}{n_i^2}) = V_t \ln(\frac{N_a N_d}{n_i^2}) \end{split}$$

 V_{bi} : built-in potential barrier; $V_t = kT/e$: thermal voltage

Charge Density

• Poisson's equation: $\frac{\mathrm{d}^2\phi(x)}{\mathrm{d}x^2} = \frac{-\rho(x)}{\epsilon_s} = -\frac{\mathrm{d}E(x)}{\mathrm{d}x}, \ \epsilon_s = \epsilon_0\epsilon_r$



volume charge density:

$$\rho(x) = \begin{cases} -eN_a, & -x_p \le x \le 0 \\ +eN_d, & 0 \le x \le x_n \end{cases}$$

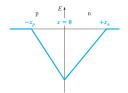
Electric Field

• electric field:

$$E(x) = \begin{cases} -\frac{eN_a}{\epsilon_s}(x + x_p), & -x_p \le x \le 0\\ -\frac{eN_d}{\epsilon_s}(x_n - x), & 0 \le x \le x_n \end{cases}$$

• continuity at x = 0:

$$N_a x_p = N_d x_n$$



• maximum electric field intensity at x = 0:

$$E_{\max} = -\frac{eN_a x_p}{\epsilon_s} = -\frac{eN_d x_n}{\epsilon_s}$$

Electric Potential

• Set $\phi(x = -x_p) = 0$:

$$\phi(x) = \begin{cases} \frac{eN_a}{2\epsilon_s} (x + x_p)^2, & -x_p \le x \le 0\\ \frac{eN_d}{\epsilon_s} (x_n \cdot x - \frac{x^2}{2}) + \frac{eN_d}{2\epsilon_s} x_p^2, & 0 \le x \le x_n \end{cases}$$

• when $x = x_n$, the potential is equal to the built-in potential barrier:

$$V_{bi} = |\phi(x = x_n)| = \frac{e}{2\epsilon_s} (N_d x_n^2 + N_a x_p^2)$$

Space Charge Width

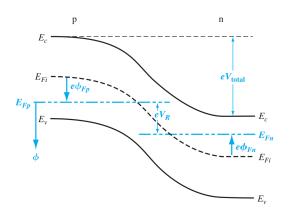
$$x_n = \sqrt{\frac{2\epsilon_s V_{bi}}{e} (\frac{N_a}{N_d}) (\frac{1}{N_a + N_d})}$$
$$x_p = \sqrt{\frac{2\epsilon_s V_{bi}}{e} (\frac{N_d}{N_a}) (\frac{1}{N_a + N_d})}$$

• total depletion region width *W*:

$$W = x_n + x_p$$

$$= \sqrt{\frac{2\epsilon_s V_{bi}}{e} (\frac{N_a + N_d}{N_a N_d})}$$

Reverse Applied Bias



• total potential barrier V_{total} :

$$V_{\mathsf{total}} = |\phi_{\mathit{Fn}}| + |\phi_{\mathit{Fp}}| + V_{\mathit{R}} = V_{\mathit{bi}} + V_{\mathit{R}}$$

Space Charge Width and Electric Field

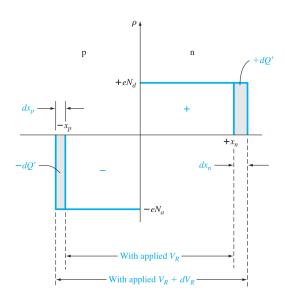
- In all of the previous equations, the built-in potential barrier can be replaced by the total potential barrier.
- total space charge width:

$$W = \sqrt{\frac{2\epsilon_s(V_{bi} + V_R)}{e}(\frac{N_a + N_d}{N_a N_d})}$$

maximum electric field:

$$E_{\text{max}} = -\sqrt{\frac{2e(V_{bi} + V_R)}{\epsilon_s}(\frac{N_a N_d}{N_a + N_d})}$$
$$= \frac{-2(V_{bi} + V_R)}{W}$$

Junction Capacitance



Junction Capacitance

- seperated +/- charges in depletion region: capacitance behavior
- The junction capacitance is defined as

$$C' = \frac{\mathrm{d}Q'}{\mathrm{d}V_R}$$

where

$$dQ' = eN_d dx_n = eN_a dx_p$$

$$C' = \sqrt{\frac{e\epsilon_s N_a N_d}{2(V_{bi} + V_R)(N_a + N_d)}} = \frac{\epsilon_s}{W}$$

• unit of C': F/cm^2

One-Sided Junctions

- If, for example, $N_a \gg N_d$, this junction is referred to as a $p^+ n$ junction.
- total space charge width reduces to

$$W pprox \sqrt{rac{2\epsilon_s(V_{bi} + V_R)}{eN_d}}$$

• Consider expressions for x_n and x_p , for p^+n junction:

$$x_p \ll x_n$$

$$W \approx x_n$$

• junction capacitance for p^+n junction reduces to:

$$C' pprox \sqrt{rac{e\epsilon_s N_d}{2(V_{bi}+V_R)}}$$

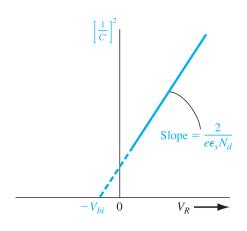
One-Sided Junctions

• The depletion layer capacitance of a one-sided junction is a function of the doping concentration in the low-doped region:

$$(\frac{1}{C'})^2 = \frac{2(V_{bi} + V_R)}{e\epsilon_s N_d}$$

 the inverse capacitance squared is a linear function of applied reverse-biased voltage: an experimental way to determine doping concentration

One-Sided Junctions



pn Junction Current

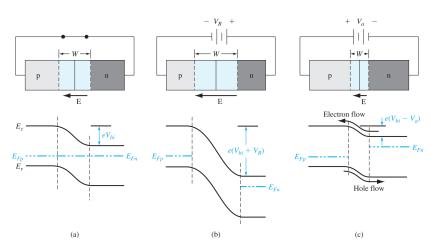


Figure 8.1 | A pn junction and its associated energy-band diagram for (a) zero bias, (b) reverse bias, and (c) forward bias.

Ideal Current-Voltage Relationship

The ideal current–voltage relationship of a pn junction is derived on the basis of four assumptions. (The last assumption has three parts, but each part deals with current.) They are:

- The abrupt depletion layer approximation applies. The space charge regions have abrupt boundaries, and the semiconductor is neutral outside of the depletion region.
- **2.** The Maxwell–Boltzmann approximation applies to carrier statistics.
- **3.** The concepts of low injection and complete ionization apply.
- **4a.** The total current is a constant throughout the entire pn structure.
- **4b.** The individual electron and hole currents are continuous functions through the pn structure.
- **4c.** The individual electron and hole currents are constant throughout the depletion region.

Notation

Table 8.1 | Commonly used terms and notation for this chapter

Term	Meaning
N_a	Acceptor concentration in the p region of the pn junction
N_d	Donor concentration in the n region of the pn junction
$n_{n0}=N_d$	Thermal-equilibrium majority carrier electron concentration in the n region
$p_{p0} = N_a$	Thermal-equilibrium majority carrier hole concentration in the p region
$p_{p0} = N_a n_{p0} = n_i^2 / N_a$	Thermal-equilibrium minority carrier electron concentration in the
2	p region
$p_{n0}=n_i^2/N_d$	Thermal-equilibrium minority carrier hole concentration in the n region
n_p	Total minority carrier electron concentration in the p region
p_n	Total minority carrier hole concentration in the n region
$n_p(-x_p)$	Minority carrier electron concentration in the p region at the space charge edge
$p_n(x_n)$	Minority carrier hole concentration in the n region at the space charge edge
$\delta n_p = n_p - n_{p0}$	Excess minority carrier electron concentration in the p region
$\delta p_n = p_n - p_{n0}$	Excess minority carrier hole concentration in the n region

Boundary Conditions

Assume complete ionization:

$$n_{n0} \approx N_d$$

• in the p region:

$$n_{p0} pprox rac{n_i^2}{N_a}$$
 $n_{p0} = n_{n0} \mathrm{exp}(rac{-eV_{bi}}{kT})$

This equation relates the minority carrier electron concentration on the p side of the junction to the majority carrier electron concentration on the n side of the junction in thermal equilibrium.

Boundary Conditions

• When a forward bias V_a is applied to the pn junction, the boundary conditions for total minority carrier concentrations are:

$$p_n(x_n) = p_{n0} \exp(\frac{eV_a}{kT})$$

$$n_p(-x_p) = n_{p0} \exp(\frac{eV_a}{kT})$$

$$p_n(x \to +\infty) = p_{n0}$$

$$n_p(x \to -\infty) = n_{p0}$$

Minority Carrier Distribution

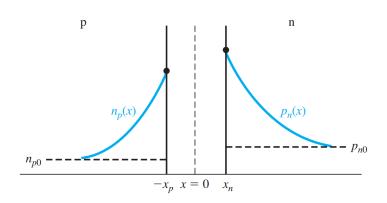
- Assume long pn junction.
- excess carrier concentrations for $x \ge x_n$:

$$\delta p_n(x) = p_n(x) - p_{n0} = p_{n0} \left[\exp\left(\frac{eV_a}{kT}\right) - 1 \right] \exp\left(\frac{x_n - x}{L_p}\right)$$

• for $x \leq -x_p$:

$$\delta n_p(x) = n_p(x) - n_{p0} = n_{p0} \left[\exp\left(\frac{eV_a}{kT}\right) - 1 \right] \exp\left(\frac{x_p + x}{L_n}\right)$$

Minority Carrier Distribution



hole diffusion current density:

$$J_p(x_n) = \frac{eD_p p_{n0}}{L_p} \left[\exp\left(\frac{eV_a}{kT}\right) - 1 \right]$$

electron diffusion current density:

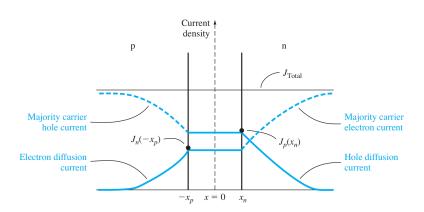
$$J_n(-x_p) = \frac{eD_n n_{p0}}{L_n} \left[\exp\left(\frac{eV_a}{kT}\right) - 1 \right]$$

• for $x \ge x_n$:

$$J_p(x) = \frac{eD_p p_{n0}}{L_p} \left[\exp\left(\frac{eV_a}{kT}\right) - 1 \right] \exp\left(\frac{x_n - x}{L_p}\right)$$

• for $x \leq -x_p$:

$$J_n(x) = \frac{eD_n n_{p0}}{L_n} \left[\exp\left(\frac{eV_a}{kT}\right) - 1 \right] \exp\left(\frac{x_p + x}{L_n}\right)$$



total current density:

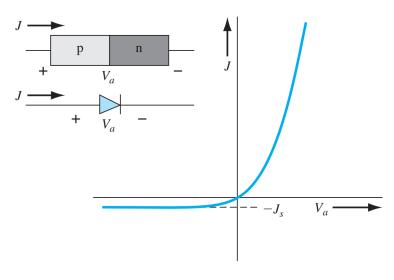
$$J = J_p(x_n) + J_n(-x_p) = \left[\frac{eD_p p_{n0}}{L_p} + \frac{eD_n n_{p0}}{L_n}\right] \left[\exp(\frac{eV_a}{kT}) - 1\right]$$

• define a parameter J_s as

$$J_s = \frac{eD_p p_{n0}}{L_p} + \frac{eD_n n_{p0}}{L_n}$$

so that the total current density can be written as:

$$J = J_s[\exp(\frac{eV_a}{kT}) - 1]$$



Reverse-Biased Generation Current

mobile electrons and holes are swept out of the space charge width:

$$n \approx p \approx 0$$

recombination rate:

$$R = \frac{-C_n C_p N_t n_i^2}{C_n n' + C_p p'}$$

• to simplify calculation, assume $E_t = E_i$, $\tau_{n0} = \tau_{p0} = \tau_0$:

$$R = \frac{-n_i}{2\tau_0} = -G$$

G: generation rate of electrons and holes in the depletion region

Reverse-Biased Generation Current

• generation current density:

$$J_{\rm gen} = \int_0^W eG \mathrm{d}x$$

• If we assume that the generation rate is constant throughout the space charge region, then we obtain:

$$J_{
m gen}=rac{en_iW}{2 au_0}$$

 The total reverse-biased current density is the sum of the ideal reverse saturation current density and the generation current density:

$$J_R = J_s + J_{\rm gen}$$

Forward-Biased Recombination Current

The recombination current density may be calculated from

$$J_{\rm rec} = \int_0^W eR \mathrm{d}x$$

• maximum recombination rate at the center of the space charge region:

$$R_{\text{max}} = \frac{n_i}{2\tau_0} \left[\exp\left(\frac{eV_a}{2kT}\right) - 1 \right]$$

recombination current density can be written as

$$J_{\text{rec}} = \frac{eWn_i}{2\tau_0} \left[\exp(\frac{eV_a}{2kT}) - 1 \right]$$

Forward-Biased Recombination Current

total forward-bias current:

$$I = I_s[\exp(\frac{eV_a}{nkT}) - 1]$$

- n: ideality factor
- diffusion dominates: $n \approx 1$
- recombination dominates: $n \approx 2$

Reference

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- 2022Summer RC_Mid2_part2, Yucheng Huang